

REMARKS

Favorable reconsideration of this application as presently amended and in light of the following discussion is respectfully requested.

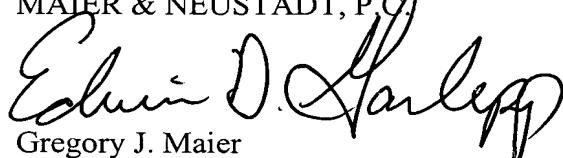
Claims 21-24 are presently active in this case, Claim 22 amended by way of the present amendment.

Claim 22 has been amended to read "said each mask pattern" to correspond to "each mask pattern" in Claim 21.

Consequently, in view of the present amendment, no further issues are believed to be outstanding in the present application and the present application is believed to be in condition for allowance. An early and favorable action is therefore respectfully requested.

Respectfully submitted,

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IN THE CLAIMS

Please amend Claim 22 as follows:

22. (Twice Amended) The method of manufacturing a semiconductor device according to Claim 21, wherein  
said each mask [patterns] pattern of said plural intellectual properties has a mark for positioning, and  
positioning of said mask patterns is performed by superposing one of said marks on another of said marks.